

TiN

TITANIUM NITRIDE SPUTTERING TARGET

TiN sputtering targets are used to make coatings, which are for edge retention and corrosion resistance on machine tooling, such as drill bits and milling cutters, often improving their lifetime by a factor of three or more. TiN are also used in microelectronics, where they serve as a conductive connection between the active device and the metal contacts used to operate the circuit, while acting as a diffusion barrier to block the diffusion of the metal into the silicon. Owing to their high biostability, TiN layers may also be used as electrodes in bioelectronic applications.

Quick Facts

Product	:	Titanium Nitride Sputtering Target
Stock No	:	NS6130-10-1331
CAS	:	25583-20-4
Backing Plate	:	(As per Customer requirement)

Additional Characteristics

Stock No.	Purity	Diameter	Thickness
NS6130-10-1331	99.99%	50.8 mm \pm 1mm	3 mm \pm 0.5mm

Technical Specification

Molecular Formula	Molecular Weight	Melting Point
TiN	61.87g/mol	2930°C



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| www.nanoshel.com | sales@nanoshel.com

INTELLIGENT MATERIALS PVT LTD

Derabassi
Punjab (140507)
INDIA

+91 9779 550077, 9779238252

NANOSHEL UK LIMITED

Chapel House,
Chapel St Cheshire,
CW12 4AB United Kingdom

+44 (0) 74 105 488, +44 203 137 5187

NANOSHEL LLC

3422 Old Capitol Suit
1305 Wilmington DE - 19808
United States

+1 646 470 4911

ISO 9001:2015
CERTIFIED COMPANY



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20ZICE4588M

High Purity
SPUTTERING
TARGET